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In the Claims:

1. (Currently Amended) A plasma processing apparatus having a vacuum chamber for generating plenty of inductively coupled plasmas therein, comprising:
a first very high frequency power source that supplies a very high frequency power having a frequency of ~~20 to 300MHz~~ ranging from more than 30 MHz to 300 MHz; and
a plurality of antenna units, each comprising a coil consisting of a single turn, being electrically parallel-connected with each other and receiving the very high frequency power from the first very high frequency power source;
an antenna being comprised of the plurality of antenna unit;
wherein the vacuum chamber has a reaction space where the inductively coupled plasmas are generated by the plurality of antenna units.
2. (Original) An apparatus according to claim 1, wherein one of the antenna units has at least one variable load that is connected in series.
3. (Original) An apparatus according to claim 2, wherein the antenna units having at least one variable load is located in an outer part of the antenna.
4. (Original) An apparatus according to claim 3, wherein the variable load is a variable capacitor.
5. (Original) An apparatus according to claim 1, further comprising an impedance matching box that is connected to the very high frequency power source and the antenna.
6. (Previously amended) An apparatus according to claim 5, wherein the parallel-connected antenna units maintain a resonance state therebetween.
7. (Original) An apparatus according to claim 6, further comprising a chuck in the vacuum chamber for mounting a substrate thereon.
8. (Original) An apparatus according to claim 7, further comprising a second very high frequency power source that supplies a very high frequency power having a frequency of 20 MHz to 300 MHz to the chuck.
9. (Currently amended) An RF power supplying apparatus, comprising:

a very high frequency power source supplying a very high frequency power having a frequency ~~of 20 MHz to 300 MHz~~ ranging from more than 30 MHz to 300 MHz;

an impedance matching box connected to the very high frequency power source;

a plurality of antenna units, each comprising a coil antenna consisting of a single turn, being electrically connected in parallel with each other; and

an antenna being comprised of the plurality of antenna units;

wherein each antenna unit has at least one variable capacitor ~~on a coil antenna.~~

Wherein the variable capacitor is located outside the coil antenna with electrically series connection with the coil antenna.

10. (Currently amended) A plasma processing apparatus having a vacuum chamber for generating plenty of inductively coupled plasmas therein, comprising:

a first very high frequency power source that supplies a very high frequency power having a frequency ~~greater than 30MHz~~ ranging from greater than 30 MHz to 300 MHz; and

a plurality of antenna units being electrically parallel-connected with each other and receiving the very high frequency power from the first very high frequency power source;

an antenna being comprised of the plurality of antenna unit;

an antenna coil in each antenna unit consisting of a single turn;

wherein each antenna unit has at least one variable capacitor that is located outside the antenna coil with electrically series connection with the coil antenna; and

wherein the vacuum chamber has a reaction space where the inductively coupled plasmas are generated by the plurality of antenna units.

11. (Currently amended) An RF power supplying apparatus, comprising:

a very high frequency power source supplying a very high frequency power;

an impedance matching box connected to the very high frequency power source ~~in parallel with each other;~~

a plurality of antenna units, each comprising an antenna coil consisting of a single turn, electrically connected in parallel with each other; ~~and~~

an antenna being comprised of the plurality of antenna units;

wherein each antenna unit has at least one variable capacitor that is located outside the antenna coil with electrically series connection with the coil antenna.